

<p style="text-align: center;">INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i></p> <p style="text-align: center;">O I P E JCT MAR 16 2005 U.S. PATENT DOCUMENTS</p>				Docket Number (Optional) 34261-8500	Application Number 10/680,960		
				Applicant(s) Howard Ge et al.			
				Filing Date 10/07/2003	Group Art Unit 1756		
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
DCD		5,032,217	7/16/1991	Tanaka			
DCD		2,046,596	7/7/1936	Zwiebel			
DCD		5,455,062	10/3/1995	Muhlfriedal et al.			
DCD		5,498,449	3/12/1996	Bae			
DCD		6,403,500	6/11/2002	Yu et al.			
U.S. PATENT APPLICATION PUBLICATIONS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
DCD		2002/0092917	7/18/2002	Ko et al.			
FOREIGN PATENT DOCUMENTS							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation
							YES NO
DCD		11-010041	19-01-1999	Patent Abstracts of Japan			✓
DCD		0 654 306	27-05-1994	Europe			✓
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
DCD		KUTCHOUKOV V G ET AL.: "New photoresist coating method for 3-D structured wafers" SENSORS AND ACTUATORS A, ELSEVIER SEQUOIA S.A., LAUSANNE, CHI, vol. 85, no. 1-3, 25 August 2000 pages 377-383.					
EXAMINER <i>/Daborah Chacko-Davis/</i>				DATE CONSIDERED 06/08/2006			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

INFORMATION DISCLOSURE/CITATION <i>(Use several sheets if necessary)</i>			Docket Number (Optional)		Application Number		
			34261-8500		10/380,960		
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			Ge et al.				
Filing Date 10/07/2003			Group Art Unit 1756				
U. S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
DCD		5,762,708	06/09/1998	Motada et al.	118	52	
DCD		6,174,561	01/16/2001	Taylor	427	96	
U. S. PATENT APPLICATION PUBLICATIONS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
FOREIGN PATENT DOCUMENTS							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation
							YES
DCD		617,332	09/28/1994	EP			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
DCD		Anonymous, "Process to Clean Metal Surfaces Prior to Photoresist Apply" (XP 007116262A) Research Disclosure – Kenneth Mason Publications, Vol. 324, No. 31, Abstract, April 1991					
DCD		Written Opinion of the International Searching Authority, the European Patent Office for the PCT counterpart application PCT/US2004/023587					
EXAMINER /Daborah Chacko-Davis/			DATE CONSIDERED 06/08/2006				
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